

SU-8 2075 – run sheet

Kayaku Advanced Materials

nanyte.com/photoresists/su-8-2075 · last updated 2026-09-13

Thickness: 59–239 μm

Softbake: 95 °C · hotplate

Exposure dose – dose by film thickness

Film thickness	Dose
25–40 μm	150–160 mJ/cm^2
45–80 μm	150–215 mJ/cm^2
85–110 μm	215–240 mJ/cm^2
115–150 μm	240–260 mJ/cm^2
160–225 μm	260–350 mJ/cm^2

Post-exposure bake: 95 °C · hotplate

Develop: Developer SU-8 Developer; ethyl lactate or diacetone alcohol may also be used · Rinse Spray and wash with fresh SU-8 developer for about 10 s, and again for another 10 s if needed, then air-dry with filtered pressurised air or nitrogen. A white film during an IPA rinse means the unexposed resist is under-developed: return it to SU-8 developer and repeat the rinse. · Method immersion, spray or spray-puddle

Hardbake: 150–250 °C · 5–30 min